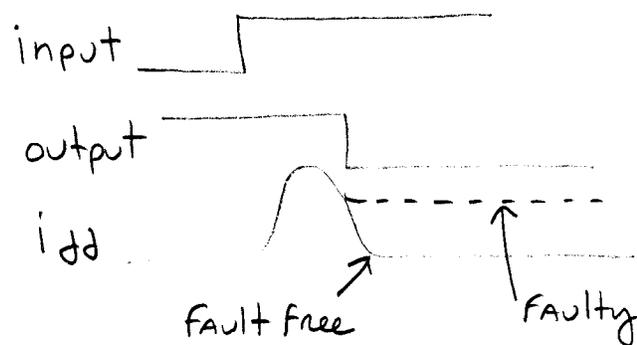
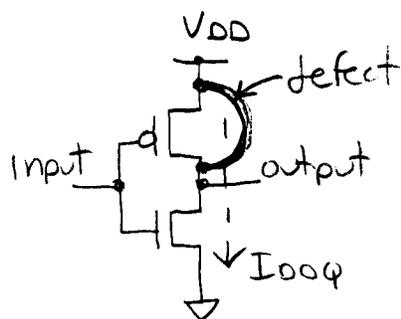


# $I_{DDQ}$ TESTING of CMOS chips

Under steady state conditions, CMOS gates do not consume power (ideally).

Some current does flow in steady state conditions that is called leakage current, denoted as  $I_{DDQ}$ .

By measuring elevated leakage current, A defective chip may be detected.



A defect that causes a high  $I_{DDQ}$  when excited is called a PATTERN dependent defect. A defect that causes a high  $I_{DDQ}$  independent of input pattern is called a PASSIVE defect.

## Advantages of Iddq Testing

Since Iddq test uses power lines for fault propagation, 100% observability is possible.

Only a relatively few vectors are required to excite all possible defect sites.

Defects detected by Iddq testing also tend to reduce reliability.

- metal slivers, electromigration damage
- hot carrier injection damage

Iddq tests are very useful to screen devices used in high reliability applications.

# I<sub>DDQ</sub> testing of DSM CMOS

## Current Signature

Run many vector sets into chip and note any large jumps in I<sub>DDQ</sub> over background current.

## Delta I<sub>DDQ</sub>

Measure difference between minimum I<sub>DDQ</sub> vector and maximum I<sub>DDQ</sub> vector; reject if difference is large.

## Wafer-level Spatial Correlation

Neighboring chips on wafer have fault-free I<sub>DDQ</sub> characteristics. Reject those neighbors outside the norm.

## Challenges to I<sub>DDQ</sub> Testing

Static threshold method traditionally used

- If I<sub>DDQ</sub> exceeds a threshold, the chip is rejected.

As feature sizes decrease, static threshold methods no longer work.

$$I_{DDQ} \approx \left( \frac{W \cdot X_c}{L_{eff}} \right) e^{-\frac{K V_T}{T}}$$

$K$  = Boltzmann const.

$W \cdot X_c$  = channel cross sectional current flow area

$W$  = channel width

$L_{eff}$  = effective channel length

$V_T$  = device threshold voltage

$T$  = device temperature

To operate with much thinner gate oxides,  $V_T$  must be reduced. This causes an exponential increase in leakage current.

For current high performance DSM technology, leakage currents are on the order of a few hundred mA.

Future technologies will produce leakage currents in the 10's of Amperes. (8 to 20 A by 2014)

I<sub>DDQ</sub> testing is slow. 10-100 m\$ per measurement